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File 350:WORLD PATENTS INDEX\_1963-1980 EQUIVALENTS THRU DW=9039

Set Items Description

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1/9/1 (Item 1 from file: 351) 4198302 WPI Acc No: 86-201691/31

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High yield 1,2-dichloropropionic acid (ester) prepn. by photochlorinating acrylic acid (ester) without using metal

Patent Assignee: (NIPE-) NIPPON PEROXIDE KK

Patent Family:

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JP 61134343 A 860621 8631 (Basic) Priority Data (CC, No, Date): JP 84255728 (841205);

Abstract (Basic): JP61134343

Acrylic acid and/or ester(s) and chlorine are supplied at a ratio of 1/0.6-1.8 to allow reaction under light irradiation. Photo-chlorination is carried out at 10-60 deg.C. Reaction is usually carried out in a solvent, pref. halogenated hydrocarbon(s). 2-5 wt. times solvent to acrylic acid (cr its ester(s)) is used. As light-source, e.g., sun-light, glow lamp, mercury lamp etc. can be used.

USE/ADVANTAGE - 1,2-Dichloropropionic acid or its ester(s) can be

prepd. in high yields without using heavy metal catalyst.

In an example, in glass reactor, with a jacket, CCl4 (500g) was placed. Under My lamp irradiation, acrylic acid and chlorine were supplied to allow react at 40 deg.C. Mol. ratio was set 1.02. 1,2-Dichloropropionic acid was obtd. in 82.6% yield. @(4pp Dwg.No.0/0)@

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